

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Ibrahim Abdulhalim, et al.
Title: Periodic Patterns And Technique To Control Misalignment Between
Two Layers
Application No.: 10/699,153 Filing Date: October 30, 2003
Examiner: Unknown Group Art Unit: 1765
Docket No.: TNCR.196US2 Conf. No.: 1463

Certificate of Mailing Under 37 CFR 1.8

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Signature Tracy Mignod

Commissioner for Patents
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Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.

Citation of these documents shall not be construed as (1) an admission that the documents are prior art with respect to the invention or inventions claimed in this application, (2) a representation that a search has been made (other than as indicated by any cited document), or (3) an admission that the cited information is, or is considered to be, material to patentability as defined in § 1.56(b).

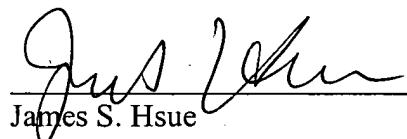
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This information disclosure statement is submitted under 37 C.F.R. § 1.97(b) and consequently no fee should be required. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

Respectfully submitted,



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3/1/04

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U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>MAR 05 2004</i>		Atty. Docket No. TNCR.196US2	Application No. 10/699,153
		Applicant(s) Ibrahim Abdulhalim, et al.	Conf. No. 1463
(Use several sheets if necessary)		Filing Date October 30, 2003	Group 1765

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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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	86	"Modeling of Optical Scatterometry with Finite-Number-of-Periods Grating", Journal: Proceedings of the SPIE, vol. 3743, p. 41-8. (Abstract)
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	92	"Kinetics of the Diffraction Efficiency of Light-Induced Dynamic Gratings in Layers of Disordered Semiconductors", Arkhipov et al., Quantum Electron, vol. 23, November 1993, p. 986-988.
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	97	"Photoreactive Optical Properties of Volume Phase Gratings Induced in Sillenite Crystals, When The Grating Vector Lies on the (111) Plane", Papzoglou et al., Applied Physics B 71, p. 841-848 (2000)
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	99	“A New Technique for Multiple Overlay Check”, Auzino et al., Microelectronic Engineering, p. 41-42. (Abstract)	
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	101	“Towards the Optimal Design of Binary Optical Elements with Different Phase Levels Using a Method of Phase Mismatch Correction”, Kodate et al., Trends in Optics and Photonics, vol. 41, p. 174-6. (Abstract)	
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<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>			